

09/295607

Sheet 1 of 2

Form PTO-1449
(Rev. 8-83)U.S. Department of Commerce
Patent and Trademark Office

Attorney D ck t No. 0756-1961

Serial No. N t Y t Assign d

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant: Shunpei YAMAZAKI t al.

Filing Date:

Group: 2812

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appr priate)
Loke	4,727,044	2/23/88	Yamazaki			
Loke	4,959,700	9/25/90	Yamazaki			
Loke	5,142,344 8-25-1992	5/24/91	Yamazaki			
Loke	4,415,383	11/15/83	Naem et al.			
Loke	4,523,962	6/18/85	Nishimura			
Loke	4,431,459	2/14/84	Teng			
Loke	4,851,363	7/25/89	Troxel et al.			
Loke	4,959,700	9/25/90	Yamazaki			2/3/88
Loke	5,306,651	4/26/94	Masumo et al.	437	40	5/10/91
Loke	4,561,906	12/31/85	Calder et al.	437	101	10/24/83
Loke	5,091,334	2/25/92	Yamazaki et al.	437	101	6/29/81
Loke	5,272,361	12/21/93	Yamazaki	257	66	6/13/90

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation Yes No
Loke	59-121876	7/14/84	Japan			Abstract
Loke	60-245174	12/4/85	Japan			Abstract
Loke	6-59280	3/4/94	Japan			Abstract
Loke	5-206468	8/13/93	Japan			Abstract
Loke	1-187983	7/27/89	Japan			Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Loke	Sameshima et al., Japanese Journal of Applied Physics, "XeCl Excimer Laser Annealing Used to Fabricate Poly-Si TFT's", Vol. 28, No. 10, October, 1989, p. 1789-1793.
Loke	Sera et al., "High Performance TFT's Fabricated by XeCl Excimer Laser Annealing of Hydrogenated Amorphous Silicon Film", IEEE Transactions, 36 (1989), p. 2868-2872.

Examiner

Loke

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Attorney Docket No. 0756-1961

Serial No. 09/295,607

Applicant: Shunpei YAMAZAKI et al.

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Filing Date: April 22, 1999

Group: 2811

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
Loke	5,147,826	09/15/92	Liu et al			
	5,275,851	01/04/94	Fonash et al			
	5,134,018	07/28/92	Tokunaga			
	4,057,895	11/15/77	Ghezso			
	5,920,781	07/06/99	Imoto			
	4,599,118	07/08/86	Han et al			
	5,830,787	11/03/98	Kim			
	4,282,646-543	08/04/81	Ihara et al			
	5,946,561	08/31/99	Yamazaki et al			
Loke	5,091,334	02/25/92	Yamazaki et al			

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation Yes No
Loke	EP 0 474 289 A1	03/11/92	Europe			
	63-258063	10/25/88	Japan			Abstract
	62-188373	08/17/87	Japan			Abstract
Loke	5-21763	01/29/93	Japan			Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Loke	Hempel et al., "Needle-Like Crystallization of Ni Doped Amorphous Silicon Thin Films", Solid State Communications, Vol. 85, No. 11, March 1993, pp. 921-924
	Hayzelden et al., "In Situ Transmission Electron Microscopy Studies of Silicide-Mediated Crystallization of Amorphous Silicon", Appl. Phys. Lett., Vol. 60, No. 2, January 13, 1992, pp. 225-227
	Dvurenchenskii et al., "Transport Phenomena in Amorphous Silicon Doped by Ion Implantation of 3d Metals", Phys. Stat. Sol. Vol. (a) 95, (1986), pp. 635-640
	Crowder et al., "DMOS FET with Common Field and Channel Doping", IBM Technical Disclosure Bulletin, Vol. 20, No. 4, September 1977, pp. 1617-1621
	Fathimulla et al., "Reactively rf Magnetron Sputtered AlN Films as Gate Dielectric", J. Appl. Phys., Vol. 54, No. 8, August 1983, pp. 4586-4589
Loke	Gerova, "Deposition of AlN Thin Films by Magnetron Reactive Sputtering", Thin Solid Films - Preparation and Characterization, Vol. 81, (1981), pp. 201-205

Examiner

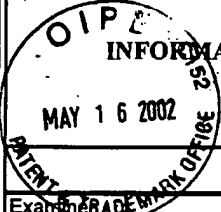
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Submitted with IDS of September 5, 2000

Form PTO-1449 (Rev. 8-83)		U.S. Department of Commerce Patent and Trademark Office		Atty Docket 0756-1961		Serial No. 09/295,607		
 <p>INFORMATION DISCLOSURE STATEMENT</p>				Applicants: Shunpei YAMAZAKI et al.				
				Filing Date: April 22, 1999		Group Art Unit: 2811		
U.S. PATENT DOCUMENTS								
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)		
<i>Loke</i> <div style="position: absolute; left: -40px; top: 50px; transform: rotate(-90deg);"> AE 4-20 09 </div>	2001/0050664	12/13/2001	Yamazaki et al.					
	4,468,855	09/04/1984	Sasaki					
	4,651,182	03/17/1987	Yamazaki					
	4,762,807	08/09/1988	Yamazaki					
	4,826,711	05/02/1989	Yamazaki et al.					
	5,313,077	05/17/1994	Yamazaki					
	5,315,132	05/24/1994	Yamazaki					
	5,409,982	04/25/1995	Imura et al.					
	5,514,879	05/07/1996	Yamazaki					
	5,536,575	07/16/1996	Imura et al.					
	5,543,636	08/06/1996	Yamazaki					
	5,569,490	10/29/1996	Imura et al.					
	5,614,732	03/25/1997	Yamazaki					
	5,652,016	07/29/1997	Imura et al.					
	5,859,445	01/12/1999	Yamazaki					
↓	6,011,277	01/04/2000	Yamazaki					
<i>Loke</i>	6,221,701	04/24/2001	Yamazaki					
FOREIGN PATENT DOCUMENTS								
Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes No		
<i>Loke</i> <div style="position: absolute; left: -40px; top: 50px; transform: rotate(-90deg);"> AE 4-20 09 </div>	0 072 216	02/16/1983	EP			Full Eng		
	0 486 284	05/20/1992	EP			Full Eng		
	02-153896	06/13/1990	JP			Eng Abst		
	03-022540	01/30/1991	JP			Full Eng		
	04-085922	03/18/1992	JP			Eng Abst		
	04-133029	05/07/1992	JP			Eng Abst		
	04-186775	07/03/1992	JP			Eng Abst		
	04-190329	07/08/1992	JP			Eng Abst		
	↓	58-023479	02/12/1983	JP			Eng Abst	
	<i>Loke</i>	58-071663	04/28/1983	JP			Eng Abst	
Examiner <i>Loke</i>				Date Considered <i>7/27/02</i>				
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